

| | Type | L # | Hits | Search Text | DBs | Time Stamp | Comments |
|---|------|-----|-------|--|--|------------------|----------|
| 1 | BRS | L1 | 14624 | (tantalum) near40 (tungsten) near15 (molybdenum) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM-TDB | 2004/01/24 13:53 | |
| 2 | BRS | L2 | 9089 | (tantalum) near30 (metal\$3) near40 (tungsten) near15 (molybdenum) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM-TDB | 2004/01/24 13:54 | |
| 3 | BRS | L3 | 23568 | (tantalum) near30 (metal\$3) near40 (tungsten) near15 (weight) near15 (molybdenum) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM-TDB | 2004/01/24 13:54 | |
| 4 | BRS | L5 | 23568 | (tantalum) near30 (metal\$3) near40 (tungsten) near15 (weight) near15 (molybdenum) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM-TDB | 2004/01/24 13:55 | |

| | Type | L # | Hits | Search Text | DBs | Time Stamp | Comments |
|---|------|-----|-------|--|---|------------------|----------|
| 5 | BRS | L6 | 10152 | (tantalum) near30 (metal\$3 near5 impurit\$3) near40 (tungsten) nnear15 (weight) near15 (molybdenum) | USPAT; US-P GPUB ; EPO; JPO; DERW ENT; IBM TDB | 2004/01/24 13:56 | |
| 6 | BRS | L7 | 10103 | (purity near3 tantalum) near30 (metal\$3 near5 impurit\$3) near40 (tungsten) nnear15 (weight) near15 (molybdenum) | USPAT; US-P GPUB ; EPO; JPO; DERW ENT; IBM TDB | 2004/01/24 13:56 | |
| 7 | BRS | L8 | 10103 | (high near1 purity near3 tantalum) near30 (metal\$3 near5 impurit\$3) near40 (tungsten) nnear15 (weight) near15 (molybdenum) | USPAT; US-P GPUB ; EPO; JPO; DERW ENT; IBM TDB | 2004/01/24 13:59 | |
| 8 | BRS | L9 | 10103 | (high near1 purity near tantalum) near30 (metal\$3 near5 impurit\$3) near40 (tungsten) nnear15 (weight) near15 (molybdenum) | USPAT; US-P GPUB ; EPO; JPO; DERW ENT; IBM TDB | 2004/01/24 13:59 | |

| | Type | L # | Hits | Search Text | DBs | Time Stamp | Comments |
|----|------|-----|------|---|---|------------------|----------|
| 9 | BRS | L11 | 2 | (high near1 purity near5 tantalum) near30 (metal\$3 near5 impurit\$3) near20 (tungsten) near15 (weight) near15 (molybdenum) | USPAT; US-P GPUB ; EPO; JPO; DERW ENT; IBM TDB | 2004/01/24 13:59 | |
| 10 | BRS | L12 | 2 | (high near1 purity near5 tantalum) near30 (metal\$3 near5 impurit\$3) near40 (tungsten) near15 (weight) near15 (molybdenum) | USPAT; US-P GPUB ; EPO; JPO; DERW ENT; IBM TDB | 2004/01/24 14:00 | |
| 11 | BRS | L13 | 6 | 5244556.pn. or 3984208.pn. or 5972288.pn. | USPAT; US-P GPUB ; EPO; JPO; DERW ENT; IBM TDB | 2004/01/24 14:01 | |
| 12 | BRS | L10 | 2 | (high near1 purity near tantalum) near30 (metal\$3 near5 impurit\$3) near20 (tungsten) near15 (weight) near15 (molybdenum) | USPAT; US-P GPUB ; EPO; JPO; DERW ENT; IBM TDB | 2004/01/24 14:04 | |

| | U | 1 | PT | P | Document ID | Issue Date | Pages | Title |
|---|--------------------------|--------------------------|--------------------------|--------------------------|------------------|------------|-------|--|
| 1 | <input type="checkbox"/> | <input type="checkbox"/> | <input type="checkbox"/> | <input type="checkbox"/> | US 6566161 B1 | 20030520 | 13 | Tantalum sputtering target and method of manufacture |
| 2 | <input type="checkbox"/> | <input type="checkbox"/> | <input type="checkbox"/> | <input type="checkbox"/> | US 6323055 B | 20020921 | 12 | Highly pure tantalum preparation method for use in manufacture of electronic capacitors, bulk capacitors, thin film capacitors |